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LeA 34,283-US

**METHOD FOR POLISHING A COMPOSITE MATERIAL CONTAINING SILICA AND
SILICON NITRIDE WITH AN ACIDIC POLISHING SLURRY**

ABSTRACT OF THE DISCLOSURE

An acidic polishing slurry for chemical-mechanical polishing, containing 0.1 to 5% by weight of a colloidal silica abrasive and 0.5 to 10% by weight of a fluoride salt, is distinguished by a higher polishing selectivity with regard to the rate at which silica is removed compared to the rate at which silicon nitride is removed compared to a conventional polishing slurry containing pyrogenic silica.